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Block copolymers of aromatic polyamides and polyethers - with functional end gps, giving films with improved mechanical properties
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Patent Family

Patent Number	Kind	Date	Application Number	Kind	Date	Week	Type
DE 2405646	A	19740814				197434	B
FR 2216316	A	19741004				197448	
JP 49105850	A	19741007				197513	
JP 50029697	A	19750325				197526	
JP 49110744	A	19741022				197541	
US 3946089	A	19760323				197614	
GB 1449315	A	19760915				197638	
JP 78032396	B	19780907				197840	
CA 1039886	A	19781003				197842	
DE 2405646	B	19790913				197938	
JP 80019948	B	19800529				198026	

Priority Applications (Number Kind Date): JP 7321584 A (19730222); JP 7315318 A (19730206)

Abstract:
DE 2405646 A

The block copolymers consists of (A) a polyamide from 50-100% m-xylylene diamine or its mixts. with p-xylylene diamine and a dicarboxylic acid component of which 50-100: mol.% consists >=16-12C aliphatic acid, and (B) 0.2-10 wt. % polyether with an amine or carboxylic gp in the >=1 end posn. and mol. wt. 2000-20,000. The copolymer has an extinction index (difference in extinction values at 400 and 800 m mu, of amorphous film divided by thickness) of 1 min., and the particles of (B) are agglomerated to a size of 10 mu max. and dispersed in the copolymer. Pref. 70-100 mol. % of the diamine consists of xylylene diamines and 70-100% of the dicarboxylic acid consists of 6-12C aliphatic acids pref. adipic acid. (B) is pref. bis-amino propyl (polyethylene oxide). The copolymers have the excellent physical and mechanical props of polymers of (A) alone, without the poor flex and fold resistance and impact resistance caused by small amts. of non-extractable oligomers in the latter.